Photomask Japan 2009

8 (Wed.)-10 (Fri.) April 2009 • Pacifico Yokohama (Annex Hall) Yokohama, Japan

Symposium Chair: Toshiyuki Horiuchi, Tokyo Denki University (Japan)
Organized by Photomask Japan and SPIE, Co-organized by BACUS and EMLC

Papers are solicited on the following and related topics:

- Materials of and for Photomasks
- Fabrication Process Steps and Equipments for Photomasks (process and equipments for developing, etching, cleaning, etc)
- Photomask Writing Tools and Technologies
- Metrology Tools and Technologies
- Inspection Tools and Technologies
- Repairing Tools and Technologies
- Mask Data Preparations
- EDA and DFM for Photomasks
- Photomasks with RET: PSM, Masks with OPC
- Photomask-relating Lithography Technologies
- NGL Masks: EUV, Nano-imprint, ML2 etc.
- Mask Strategies and Business Challenges: Cost, Cycle-Time etc.

Tentative Program

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<th>Technical Conferences</th>
<th>Technical Exhibition</th>
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<td>8 April (Wed.) 9:00 am to 8:00 pm</td>
<td>8 April (Wed.), 10:00 am to 6:30 pm</td>
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<td>Poster Session (4:00 pm – 6:30 pm)</td>
<td>9 April (Thu.), 10:00 am to 4:00 pm</td>
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<td>(6:30 pm – 8:00 pm)</td>
<td>Banquet</td>
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<td>9 April (Thu.) 9:00 am to 8:00 pm</td>
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<td>Panel Discussion (6:00 pm – 8:00 pm)</td>
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All abstracts are to be registered electronically via the PMJ website to get the qualification for abstract submission to the conference.

See the reverse page for more information ➔
PMJ Website will begin accepting abstracts: 17 October (Fri), 2008

* Abstract Due Date: 14 November 2008
* Camera-Ready Abstract Due Date: 30 January 2009
* Manuscript Due Date: 12 March 2009

All abstracts must be registered electronically with the
PMJ website at: http://www.photomask-japan.org/

If electronic submission is not possible then authors are asked to
contact the Photomask Japan Secretariat before the abstract due
date.

All authors are strongly encouraged to submit their abstract
by 14 November 2008.

Please note: the electronic abstract submission system will
close on time and late abstracts will not be accepted.

Camera-ready abstracts and manuscripts are required of all
accepted applicants and must be submitted in English.

Please note: This information is subject to change without notice.

PMJ requests all prospective authors to regularly check the PMJ
website for updates.

To submit an abstract:

Abstracts must be written and presented in English.

All abstracts must be registered electronically in a PDF file via the
conference website. For registration information, please visit the
PMJ website.

Abstract Submission Information:

http://www.photomask-japan.org/

Sample Abstract Format:

(1) Title
(2) Complete Author List
E.g., Kunihiro Hosono, Renesas
Technology Corp., (Japan) Kokoro Kato,
SII Nano Technology Inc. (Japan);
Toshio Konishi, Toppan Printing Co, Ltd.
(Japan);

(3) Abstract Text
(4) Keyword(s)

(1) and (2) should be
centered on the page.

(2) Authors’ names should
be spelled out completely.

(3) should be 250 words.

Notification of Acceptance:

The Photomask Japan Program Committee will review all
contributed abstracts. Applicants will be notified of acceptance or
rejection by e-mail no later than the end of December 2008.

Abstract Submission Office:
Photomask Japan Secretariat
c/o ICS Convention Design, Inc.
Sumitomo Corp., Jinbocho Bldg.
3-24, Kanda-Nishikicho, Chiyoda-ku,
Tokyo 101-8449, Japan
Phone : +81-3-3219-3539
Fax : +81-3-3219-3626
E-mail : pmj-p@ics-inc.co.jp
Website : http://www.photomask-japan.org/

Your Abstract Reference Number will be automatically sent to
you via e-mail as soon as your application has been received
through the web page. If you do not receive a response within 24
hours, please contact the Secretariat.

All abstracts must contain the following information:

1. Title of Abstract:
   Title should be in bold font using both upper and lower
   case.

2. Names of All Authors:
   Names should be grouped by affiliation, listing Principal
   Author first. Please include both family and given names.

3. Abstract Text and Figures:
   Text should be approximately 250 words. One additional
   page for figures is acceptable.

4. Keywords:
   List maximum of five keywords. Please choose at least one
   keyword for your abstract.